

### ABSTRACT OF DISCLOSURE

The method according to the invention comprises forming on a  $\text{SiO}_x\text{F}_y$  layer a silica  $\text{SiO}_2$  and/or metal oxide protective layer obtained through ion beam-assisted vapor phase deposition, comprising bombarding the layer being formed with a beam of positive ions formed from a rare gas, oxygen or a mixture of two or more of such gases, or through cathodic sputtering of a silicon or metal layer followed by an oxidation step of the silicon or the metal layer.

Application to the production of antireflection coatings.